

OPEN KNOWLEDGE PROGRAM

MODULE 6

OVERVIEW ON NANOFABRICATION PROCESSES, TOOLS AND FACILITIES



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ICN2 Nanofabrication Facilities: from present to future

We will present the main nanofabrication techniques currently available at ICN2. Electron beam lithography system will be shown as a major nanofabrication system together with the thin film ebeam evaporator. We will explain the main applications of the oxygen plasma cleaner and the more basic optical microscope and wire bonding system will be also detailed. AFM tool will be presented as the main surface nano-characterisation technique. The policy rules for the use of the different systems will be explained.

In the second part of the talk the future nanofabrication cleanroom facility will be shown making emphasis on the overall objective of this infrastructure. Reactive Ion etching, UV laser lithography and profilometer as the main new systems to be purchase and installed in this new facility will be specified and new techniques and applications associated to them will be detailed.



Thursday October 13, 2016 - 12:00h
ICN2 Seminar Hall, ICN2 Building

Participate in this pioneering initiative!

ICN2 attendees: Please, confirm your attendance by sending an e-mail to: training@icn2.cat

External attendees: [Register here](#) to book your place.
(limited to 25 people)

Module coordinated by
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